

REMARKS

Independent Claim 1 stands rejected under 35 U.S.C. §103(a) as being unpatentable over Korean Patent Publication No. 2000-25706 (hereinafter "25706 Publication" in view of U. S. Patent No. 6,203,613 to Gates *et al.* (hereinafter "Gates").

Claim 1, as amended, recites that a first metal oxide layer is formed on a first surface portion of the insulation layer without forming the first metal oxide layer on a second surface portion of the insulation layer, such that the first metal oxide layer and the second surface portion of the insulation layer do not overlap.

The metal oxide **22** shown in the 25706 Publication has portions thereof disposed on an upper surface of the upper electrode **16**. In sharp contrast with the recitations of Claim 1, these portions of the metal oxide **22** on the upper surface of the upper electrode **16** overlap a non-exposed portion of the insulating layer **14**. Applicant further submits that Gates fails to provide the teachings missing from the 25706 Publication.

Accordingly, for at least the foregoing reasons, Applicant respectfully submits that independent Claim 1 is patentable over the 25706 Publication and Gates, and that dependent Claims 2 - 13 are patentable for at least the reason that they depend from an allowable claim.

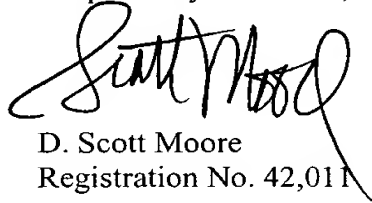
CONCLUSION

In light of the above amendments and remarks, Applicant respectfully submits that the above-entitled application is now in condition for allowance. Favorable reconsideration of this application, as amended, is respectfully requested. If, in the opinion of the Examiner, a telephonic conference would expedite the examination of this matter, the Examiner is invited to call the undersigned attorney at (919) 854-1400.

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Serial No.: 09/893,035
Filed: June 27, 2001
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It is not believed that an extension of time and/or additional fee(s), including fees for net addition of claims, are required, beyond those that may otherwise be provided for in documents accompanying this paper. In the event, however, that an extension of time is necessary to allow consideration of this paper, such an extension is hereby petitioned under 37 C.F.R. §1.136(a). Any additional fees believed to be due in connection with this paper may be charged to our Deposit Account No. 50-0220.

Respectfully submitted,



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PATENT TRADEMARK OFFICE

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: BOX RCE, Commissioner for Patents, Washington, DC 20231, on January 30, 2003.



Traci A. Brown

Date of Signature: January 30, 2003

VERSION WITH MARKINGS TO SHOW CHANGES MADE

Please amend the following claims by adding the language that is underlined ("___") and by deleting the language that is enclosed within brackets ("[]"):

1. (Amended) A method of manufacturing an integrated circuit device, comprising:

forming an insulation layer that comprises oxygen between upper and lower conductive layers, the insulation layer having a first surface portion that is exposed by the upper and lower conductive layers and a second, non-exposed, surface portion; and

exposing the insulation layer to a metal precursor that is reactive with oxygen so as to form a first metal oxide layer on the first surface portion of the insulation layer without forming the first metal oxide layer on the second surface portion of the insulation layer, such that the first metal oxide layer and the second surface portion of the insulation layer do not overlap.